Divisional of Applic. No.

Attorney Docket No.:

FORM PTO-1449 (SUBSTITUTE)

GR 97 P 1861 09/110.052 U.S. DEPARTMENT OF COMMERCE Applicant PATENT AND TRADEMARK OFFICE Volker Weinrich et al. INFORMATION DISCLOSURE Filing Date of Divisional Group Art Unit STATEMENT BY APPLICANT 2815 1746 August 24, 2000 (37 CFR 1.98(b)) SUB FILING EXAMINER PATENTEE CLASS **CLASS** DATE DATE PATENT NO. **INITIALS** Yuito et al. 07/88 4,760,481 Α **ラA** 5,057,455 10/91 Foo et al. В 06/92 Douglas \mathbf{C} 5,122,225 04/93 Kobeda et al. 5,208,170 D Prall et al. 08/94 E 5,341,016 F 09/94 Brassington et al. 5,350,705 Yokoyama et al. 05/96 G 5,515,984 10/96 Nulty Η 5,562,801 12/96 Summerfelt I 5,585,300 FOREIGN PATENT DOCUMENT TRANSL. SUB YES | NO COUNTRY **CLASS** CLASS DATE DOCUMENT NO. J K L M N OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.) Patent Abstracts of Japan No. 1-232729 A (Sakota), dated September 18, 1989. 51 "Etching of TiN local Interconnects Using HBr in a Triode Reactor with Magnetic Confinement" (Zwicker et al.), Proceedings of the International SA Society for Optical Engineering, Vol. 1803, 1992, pp. 97-106 DATE CONSIDERED EXAMINER Shamim 3/14/02 EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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SA	A	5,621,606	04/97	Hwang							
54	В	5,717,236	02/98	Shinkawata							
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5A		"Reactive Ion Etching Mechanism of Plasma Enhanced Chemically Vapor Deposited Aluminum Oxide Film in CF ₄ /O ₂ Plasma" (Kim et al.), J. Applied Physics, Vol. 78, No. 3, August 1995, pp. 2045-49.									
SA		"Local Plasma O Line Pattern Inve	"Local Plasma Oxidation and Reactive Ion Etching of Metal Films for Ultrafine Line Pattern Inversion and Transfer" (Nulman et al.), J. Vacuum Science Technology, Vol. B1, OctDec. 1983, pp. 1033-36.								
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SA		"WSi ₂ /Polysilicon (Gate Etchi	ng Using TiN Hard	Mask in C	onjunction	with	
		Photoresist" (Tabai	ra), J. App	lied Physics, Vol. 36	5, 1997, pj	o. 2508-13		
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